

School Announcement

Ion Implantation Science & Technology (with annealing)

September 22-24, 2022
San Diego, California USA

A three-day school on fundamental and practical aspects of ion implantation and annealing operations in research and IC production environments will be held prior to the 23rd International Conference on Ion Implantation Technology in San Diego, California, USA, in September 2022.

This school, which has preceded IIT meetings since 1982, will be taught by an expert group of a dozen instructors with many years of hands-on experience in the design, construction and operation of ion implantation and annealing tools as well as practical experience in process development and metrology.

All attendees of the school will receive a hardbound, ~600 page book containing tutorial chapters written by the instructors for follow-on study.

Topics covered in the course include:

- History of Integrated Circuits and Ion Implantation
- Ion Implantation: Current and Future CMOS Logic ICs
- Commercial Ion Implantation Systems
- Case Histories in Development of Ion Implantation Technology
- Science of Ion Implantation Damage and Annealing
- Annealing Process for Ion Implanted Si, Ge, SiC and GaN
- Cluster Ion Beams: History and Technology
- Ion Transport and Beam Controls
- Source Physics and Maintenance
- Safety Considerations in Ion Implantation
- Ion Beam Purity and Elemental Contamination
- Ion Implant Applications for CMOS Memory and Image Sensors
- Ion Implantation in Power Devices, new Base Materials and Solar Cells
- CMOS Scaling to 2 nm Node & Beyond

Detailed registration information will be posted as it becomes available.